

The listing of the claims will replace the previous version, and the listing of the claims:

LISTING OF THE CLAIMS

1. (currently amended) A transparent electroconductive film comprising:

a polymer film;

a primary layer ~~formed~~ coated on said polymer film and containing ultraviolet-curing resin and particles of at least one silicon compound having an average diameter of 1 nm to 5 μ m and selected from the group consisting of SiC_x , SiO_x , SiN_x , SiC_xO_y , SiC_xN_y , SiO_xN_y , and $\text{SiC}_x\text{O}_y\text{N}_z$, said particles of at least one silicon compound being included in 1-90 wt% to said ultraviolet-curing resin; and

B5 a transparent electroconductive thin film formed on said primary layer.

2-4. (cancelled)

5. (previously amended) A transparent electroconductive film as claimed in claim 1, wherein said primary layer has a thickness of 1 nm to 50 μ m.

6. (cancelled)

7. (original) A transparent electroconductive film ~~as claimed in claim 6,~~ wherein comprising:

a polymer film;

a primary layer coated on said polymer film and containing ultraviolet-curing resin and particles of at least one silicon compound having an average diameter of 1 nm to 5 μ m and selected from the group consisting of SiC_x , SiO_x , SiN_x , SiC_xO_y , SiC_xN_y , SiO_xN_y , and $\text{SiC}_x\text{O}_y\text{N}_z$, said particles of at least one silicon compound being included in 1-90 wt% to said ultraviolet-curing resin, each of said

particles of silicon compound ~~is~~ being provided with acryl groups, epoxy groups or carboxyl groups on its surface; and

a transparent electroconductive thin film formed on said primary layer.

8.(original) A transparent electroconductive film as claimed in claim 7, wherein said particles of silicon compound are particles of acryl-modified silica which are produced by condensing colloidal silica and acryl group-modified silane compound.

9.(cancelled)

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10.(currently amended) A transparent electroconductive film as claimed in claim 5 1, wherein said primary layer has a thickness of 1 nm to 10 μ m.

11.(previously amended) A transparent electroconductive film as claimed in claim 1, wherein said electroconductive thin film consists of metal oxide.

12.(original) A transparent electroconductive film as claimed in claim 11, wherein said metal oxide is at least one selected from the group consisting of ITO, ATO, ZnO, ZnO doped with Al, and SnO₂.

13.(previously amended) A transparent electroconductive film as claimed in claim 11, wherein said electroconductive thin film has a thickness of 1 to 500 nm.

14-21.(cancelled)

22.(currently amended) A transparent electroconductive film comprising:

a polymer film;

a primary layer ~~formed~~ coated on said polymer film and containing ultraviolet-curing resin and particles of at least one silicon compound having an average diameter of 1 nm to 5 μ m and selected from the group consisting of SiC_x , SiO_x , SiN_x , SiC_xO_y , SiC_xN_y , SiO_xN_y , and $\text{SiC}_x\text{O}_y\text{N}_z$, said particles of at least one silicon compound being included in 1-90 wt% to said ultraviolet-curing resin; and

a multi-lamination film comprising at least one metal-compound layer and at least one electroconductive-metal layer, formed on said primary layer.

23-25. (cancelled)

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26. (previously amended) A transparent electroconductive film as claimed in claim 22, wherein said primary layer has a thickness of 1 nm to 50 μ m.

27. (cancelled)

28. (currently amended) A transparent electroconductive film as claimed in claim ~~27~~ 22, wherein each of said particles of silicon compound is provided with acryl groups, epoxy groups or carboxyl groups on its surface.

29. (original) A transparent electroconductive film as claimed in claim 28, wherein said particles of silicon compound are particles of acryl-modified silica which are produced by condensing colloidal silica and acryl group-modified silane compound.

30. (cancelled)

31. (currently amended) A transparent electroconductive film as claimed in claim ~~27~~ 22, wherein said primary layer has a thickness of 1 nm to 10 μ m.

32.(previously amended) A transparent electroconductive film as claimed in claim 22, wherein said metal-compound layer is made up of at least one selected from the group consisting of ITO, In_2O_3 , SnO_2 , ZnO , TiO_2 , SiO_2 and SiN .

33.(previously amended) A transparent electroconductive film as claimed in claim 22, wherein said metal-compound layer is made up of composite metal composed of at least two selected from the group consisting of ITO, In_2O_3 , SnO_2 , ZnO , TiO_2 , SiO_2 and SiN .

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34.(previously amended) A transparent electroconductive film as claimed in claim 22, wherein said electroconductive-metal layer is made up of at least one selected from the group consisting of Ag, Au, Pt, Cu, Al, Cr, Ti, Zn, Sn, Ni, Co, Hf, Nb, Ta, W, Zr, Pb, Pd and In.

35.(currently amended) A transparent electroconductive film as claimed in claim 22, wherein said multi-lamination film is composed of metal-compound layers and electroconductive-metal layers which are laminated on, alternately.

36-40.(cancelled)

41.(new) A transparent electroconductive film as claimed in claim 1, wherein said at least one silicon compound is selected from the group consisting of SiC_x , SiN_x , SiC_xO_y , SiC_xN_y , SiO_xN_y , and $\text{SiC}_x\text{O}_y\text{N}_z$.

42.(new) A transparent electroconductive film as claimed in claim 22, wherein said at least one silicon compound is selected from the group consisting of SiC_x , SiN_x , SiC_xO_y , SiC_xN_y , SiO_xN_y , and $\text{SiC}_x\text{O}_y\text{N}_z$.
